2342-0107P

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Mitsuhiro HIRANO

Conf. No.:

3165

Appl. No.:

08/813,200

Group:

2814

Filed:

March 7, 1997

Examiner:

S. Rac

For:

SUBSTRATE PROCESSING APPARATUS WITH LOCAL EXHAUS

FOR REMOVING CONTAMINANTS

AMENDMENT

Honorable Commissioner for Patents Washington, D.C. 20231

January 16, 2003

Sir:

In response to the Office Action dated July 16, 2002, the period for reply extended three (3) months to January 16, 2003, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE CLAIMS:

Please replace claims 11 and 16 with the following amended claims: Please note that claims 11 and 16 are presented below in their amended form. They are further presented as an Attachment to the Amendment whereby the amendments to the claims are outlined using the conventional method of bracketing and underlining.

- 11. (Six Times Amended) A substrate processing apparatus comprising:
- chamber:

substrate processing chamber for processing substrate; a load lock chamber; a gas supply for supplying gas into said load lock

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